NanoFab at the University Ottawa

Director: Pierre Berini (pberini@uottawa.ca) | Admin. Assistant: Betty Yakimenko (nanofabadmin@uottawa.ca)
Advanced Research Complex (ARC)

- $100M building dedicated to research that opened in September 2014
- Home to the NanoFab Core Facility
  - ARC 329, ARC 330, ARC 333
- ARC was constructed with research in mind:
  - **The slightest vibration can affect laser experiments**
    - Built on anti-vibration floating floors
      - Raft slabs anchored by concrete-filled steel piles driven into the bedrock
        - If the building shakes, the slab stays put
  - **No ambient light which can affect laser experiments**
    - Some labs are nestled into the slope of a hill
  - **Labs are equipped with diffusers**
    - Push the air sideways (instead of downward) to avoid disrupting sensitive lasers
  - **Air pressure**
    - Clean Rooms kept at a positive pressure
    - Air leaks out of the labs instead of unfiltered air coming in

www2.uottawa.ca/research-innovation/nanofab
**NanoFab**

- Only open facility in Ottawa with a nanoscale focus
  - Complementary to existing facilities at local universities and government labs
- Open for collaboration with academia (professors, students, PDF’s), government and industry, with open access and fee-for-service options for both internal and external users
- Staff: Director, Administrative Assistant, Lab Technologists

- Emphasis on nano-structuring and nano-characterization:
  - Integrated optical structures
  - Lasers and biosensors
  - Waveguides
  - Metasurfaces
  - Photodetectors
  - Modulators

- NanoFab capabilities:
  - Processing of up to 4” diameter wafers & pieces
  - Electron-beam lithography
  - Focussed ion beam milling
  - Microscopy
  - Material etching
  - Material deposition
  - Back-end processing
  - Optical parameter characterisation

www2.uottawa.ca/research-innovation/nanofab
NanoFab Facilities

- **Clean Room – ARC 333** (136 m²)
  - Fabrication and characterization
  - Yellow Clean Room & White Clean Rooms (x2)
  - Class 10,000

- **Wet Chemistry lab – ARC 330** (43 m²)
  - Back-end processing

- **Metrology lab – ARC 329** (55 m²)
  - Characterization and back-end processing

www2.uottawa.ca/research-innovation/nanofab
NanoFab – Clean Rooms

Vestibule for gowning up

Yellow Clean Room

White Clean Room 1

White Clean Room 2

www2.uottawa.ca/research-innovation/nanofab
NanoFab – Yellow Clean Room

Used for fabrication and lithography work – no UV light

Other Tools for Resist Processing:

- Vacuum curing oven
- HMDS and image reversal oven
- Spinner & Hotplates
- Glove Box
- Ultrasonic Bath

Mask Aligner - OAI Model 204IR
Used for Optical Lithography

www2.uottawa.ca/research-innovation/nanofab
NanoFab – White Clean Room 1

Used for fabrication and characterisation

Other fabrication tools:
- SAMCO RIE-10NR Etching System (Reactive ion etching - Polymers & dielectrics)
- Oxygen Plasma Etcher
- Material Sputtering System – Quorum 150R
- Rapid Thermal Annealing System (150 to 1150 °C)

Other characterisation tools:
- Dektak Profilometer (surface roughness)
- Zeiss Axio Imager (for optical microscopy)

www2.uottawa.ca/research-innovation/nanofab
NanoFab – White Clean Room 2

Used for fabrication and characterisation

ORION NanoFab HIM/FIB
Focused ion beam milling & Helium ion microscopy (He / Ga columns)

AFM Park NX10
Non-contact Atomic force microscopy

Other fabrication tools:
- AML-AWB Wafer Bonder

www2.uottawa.ca/research-innovation/nanofab
NanoFab – Wet Chemistry Lab

Back-end processing for sample preparation

Tools:

- High Precision Dicing Saw
- Polishing Machine - Ultratec
- Polishing / Grinding station – Allied High Tech
- Solder Reflow Station
- Fumehood
- Electroplating System

www2.uottawa.ca/research-innovation/nanofab
NanoFab – Metrology Lab

Used for characterization and back-end processing

Zeiss GeminiSEM 500
Scanning electron microscope with Bruker EDS capabilities (Quantax)

AFM Bruker Dimension Icon
Atomic force microscopy for larger samples

Other characterisation tools:
- Metricon
  - Refractometer – measures thickness and refractive index
- Ellipsometer - Horiba UVISEL 245-2100 nm
  - For scanning spectroscopie - thin film characterization

Other back-end processing tools:
- West Bond Wire Bonder

www2.uottawa.ca/research-innovation/nanofab